

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-2 (Canceled).

Claim 3 (Currently Amended). A cleaning apparatus for cleaning an exhaust gas coming from a production apparatus configured to produce ~~for producing~~ a gallium nitride film semiconductor ~~by subjecting~~ subjected to a gallium chloride gas as a gallium source ~~which is~~ generated through the circulation of a hydrogen chloride gas over a metallic gallium to vapor phase deposition through a ~~the~~ reaction with ammonia so as to form a gallium nitride film, wherein an electroconductive corrosion-resistant material is used as the constructional material for a pipe to transport said exhaust gas ~~introduction piping~~, and said ~~introduction piping~~ pipe is electrically grounded in order to prevent an electrostatic charging generated by friction between ammonium chloride powders and inside walls of an exhaust gas passageway.

Claim 4 (Canceled).

Claim 5 (Previously Presented). The cleaning apparatus according to claim 3, wherein the cleaning apparatus is a wet absorptive cleaning apparatus.

Claims 6-8 (Canceled).

Claim 9 (Canceled).

Claim 10 (Currently Amended). The cleaning apparatus according to claim 3, further comprising:

detecting means for sampling exhaust gas circulating in the cleaning apparatus, or production apparatus, and detecting oxygen in said exhaust gas or measuring a concentration of oxygen therein.

Claim 11 (Currently Amended). The cleaning apparatus according to claim 3, wherein the electroconductive corrosion-resistant material is selected from the group consisting of stainless steel, and high nickel steel, an electroconductive resin, and a metallic material coated with an electroconductive resin.

Claim 12 (Canceled).

Claim 13 (Currently Amended). The cleaning apparatus according to claim ~~12~~11, wherein a specific volume resistivity of said electroconductive corrosion-resistant material is approximately 100  $\Omega$  cm.

Claim 14 (Previously Presented). The cleaning apparatus according to claim 3, wherein a specific volume resistivity of said electroconductive corrosion-resistant material is at most  $1 \times 10^9 \Omega$  cm.

Claim 15 (Previously Presented). The cleaning apparatus according to claim 14, wherein the specific volume resistivity is at most  $1 \times 10^7 \Omega$  cm.

Claim 16 (New). A cleaning apparatus configured to clean a gas containing an ammonium chloride powder, the cleaning apparatus comprising:

an absorption column;

a first inlet pipe configured to transport the gas containing the ammonium chloride powder into the absorption column, the first inlet pipe being made of an electroconductive corrosion-resistant material;

an outlet pipe to exhaust gases from the cleaning apparatus; and

a second inlet pipe to introduce an absorption liquid into the absorption column, wherein the first inlet pipe is electrically grounded in order to prevent an electrostatic charge generated by friction between the ammonium chloride powder and the first inlet pipe.

Claim 17 (New). A combination of a cleaning apparatus and a gas containing an ammonium chloride powder, the combination comprising:

the gas containing the ammonium chloride powder;

an absorption column;

a first inlet pipe configured to transport the gas containing the ammonium chloride powder into the absorption column, the first inlet pipe being made of an electroconductive corrosion-resistant material;

an outlet pipe to exhaust gases from the cleaning apparatus; and

a second inlet pipe to introduce an absorption liquid into the absorption column, wherein the first inlet pipe is electrically grounded in order to prevent an electrostatic charge generated by friction between the ammonium chloride powders and the first inlet pipe.